



# 제 30회 한국반도체학술대회

The 30th Korean Conference on Semiconductors

2023년 2월 13일(월)~ 15일(수) | 강원도 하이원리조트(그랜드호텔 컨벤션타워)

2023년 2월 15일(수), 09:00-10:30

Room B (에메랄드 II+III, 5층)

## D. Thin Film Process Technology 분과

### [WB1-D] Thin Films Transistors I

좌장: 박민혁 교수(서울대학교), 백인환 교수(인하대학교)

<b>WB1-D-1</b> 09:00-09:15	<b>Influence of RF Power in the Sputter-deposition of Amorphous InGaZnO Film on Transient Drain Current of Amorphous InGaZnO Thin-film Transistors</b> Da Yeon Lee, Jingyu Park, Sangwon Lee, Seung Joo Myoung, Sung-Jin Choi, Jong-Ho Bae, Dong Myong Kim, and Dae Hwan Kim <i>School of Electrical Engineering, Kookmin University</i>
<b>WB1-D-2</b> 09:15-09:30	<b>Interface Improvement in Thin Film Transistors of Atomic Layer Deposited High-k/SnO</b> Seung Ho Ryu <sup>1,2</sup> , Jihoon Jeon <sup>1,2</sup> , Taeyong Eom <sup>3</sup> , Taek-Mo Chung <sup>3</sup> , In-Hwan Baek <sup>4</sup> , and Seong Keun Kim <sup>1,2</sup> <sup>1</sup> KU-KIST Graduate School of Converging Science and Technology, Korea University, <sup>2</sup> Electronic Materials Research Center, KIST, <sup>3</sup> Thin Film Materials Research Center, KRICT, <sup>4</sup> Inha University
<b>WB1-D-3</b> 09:30-09:45	<b>8-inch Wafer Scale a-IGZO TFTs Applicable to NO<sub>2</sub> Gas Sensors</b> Jeonghee Ko <sup>1</sup> , Yongwoo Lee <sup>1</sup> , Hanbin Lee <sup>1</sup> , Yulim An <sup>1</sup> , Hyo-In Yang <sup>1</sup> , Dong Myong Kim <sup>1</sup> , Dae Hwan Kim <sup>1</sup> , Jong-Ho Bae <sup>1</sup> , Min-Ho Kang <sup>2</sup> , and Sung-Jin Choi <sup>1</sup> <sup>1</sup> School of Electrical Engineering, Kookmin University, <sup>2</sup> Department of Nano-process, NNFC
<b>WB1-D-4</b> 09:45-10:00	<b>Electro-Photo-Controlled InTiO Synaptic TFTs with Graded AlSiO<sub>x</sub> Gate Dielectric</b> Chohyeon Park <sup>1,2</sup> and Jung Wook Lim <sup>1,2</sup> <sup>1</sup> ETRI, <sup>2</sup> University of Science and Technology (UST)
<b>WB1-D-5</b> 10:00-10:15	<b>Comparative Study on Cation Composition-Dependent Contact Property of Thin-Film Transistors Using Atomic-Layer Deposited In-Ga-Zn-O Channel</b> Dong-Hee Lee <sup>1</sup> , Young-Ha Kwon <sup>2</sup> , Nak-Jin Seong <sup>2</sup> , Kyu-Jeong Choi <sup>2</sup> , Gyungtae Kim <sup>3</sup> , and Sung-Min Yoon <sup>1</sup> <sup>1</sup> Kyung Hee University, <sup>2</sup> NCD Co., Ltd., <sup>3</sup> NNFC
<b>WB1-D-6</b> 10:15-10:30	<b>A Study on the Correlation and Mechanism between Hydrogen Introduction and Improvement of Electrical Properties in InGaZnO Thin Film Transistor</b> Hee Yeon Noh, Jung-Hwa Cha, June-Seo Kim, Myoung-Jae Lee, and Hyeon-Jun Lee <i>Division of Nanotechnology, DGIST</i>